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26 March 2005

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Date

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventors:	Tina J. Wagner et al.	Date:	26 March 2005
Serial No.:	10/605,100	Art Unit:	2818
Filing Date:	09 September 2003	Examiner:	David Vu
Confirmation No.:	2099	Docket No.:	FIS920030249US1
Title:	Method of Manufacture of Raised Source Drain MOSFET with Top Notched Gate Structure Filled with Dielectric Plug In and Device Manufactured Thereby	Attorney:	Graham S. Jones, II 42 Barnard Avenue Poughkeepsie, NY 12603-5023

AMENDMENT

The Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Your Honor:

In response to the Office Action of 1 March 2005, please amend the above-identified application as follows:

Amendments to the Title begin on page 2 of this paper.

Amendments to the Abstract begin on page 3 of this paper

Amendments to the Specification begin on page 4 of this paper

Amendments to the Claims begin on page 9 of this paper.

Remarks/Arguments begin on page 14 of this paper.

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	Serial No.:	10/605,100	Art Unit:	2818

IN THE TITLE

Please amend the title to read as follows:

-- Method of Manufacture of A Raised Source Drain MOSFET with Top Notched Notch Formed on Top of Gate Structure Filled with a Dielectric Plug in and Device Manufactured Thereby - -